

Supporting Information

Area and Power Efficient Ternary Serial Adder Using Phase Composite ZnO Stack Channel FETs

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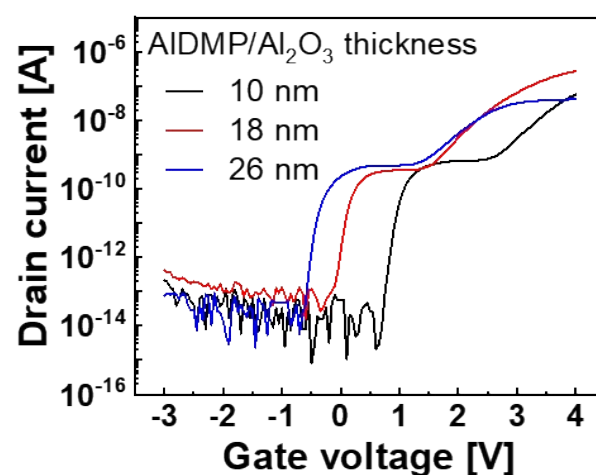


Fig. S1. Effect of the Al-DMP/ Al_2O_3 separation layer thickness on the SCFET characteristics.

The thickness of the Al-DMP/ Al_2O_3 SL significantly affected the characteristics of the SCFET. As the thickness increased, $V_{\text{th},1}$ rapidly shifted towards negative side, and it became difficult to maintain the enhancement mode operation.

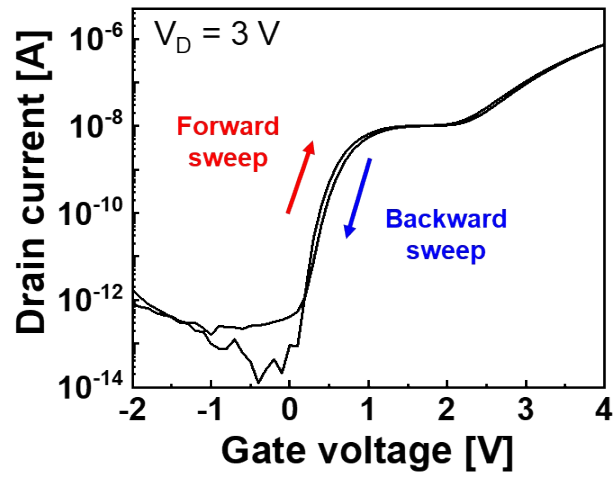


Fig. S2. Experimental I_D – V_G characteristics of the ZnO SCFETs obtained from bidirectional I – V sweep. The first and second ZnO layer thicknesses were 3.6 nm and 3.2 nm, respectively.

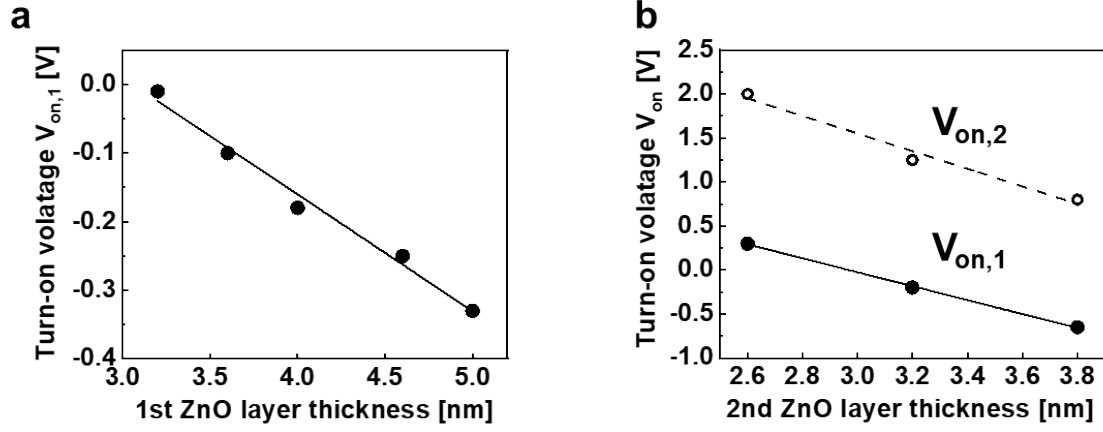


Fig. S3. a) Correlation between the thickness of the first ZnO layer and turn-on voltage 1. b) Correlation between the thickness of the second ZnO layer and turn-on voltages 1 and 2.

$$V_{on,1} = -0.1703 t_1 - 0.792 t_2 + 2.87 \quad (1)$$

$$V_{on,2} = -t_2 + 4.55 \quad (2)$$

Equation (1), extracted from the experimental data, expresses the correlation between the turn-on voltage 1 ($V_{on,1}$) and thicknesses of the first and second ZnO layers.

Further, Equation (2), extracted from the experimental data, expresses the correlation between $V_{on,2}$ and the thickness of the second ZnO layer.

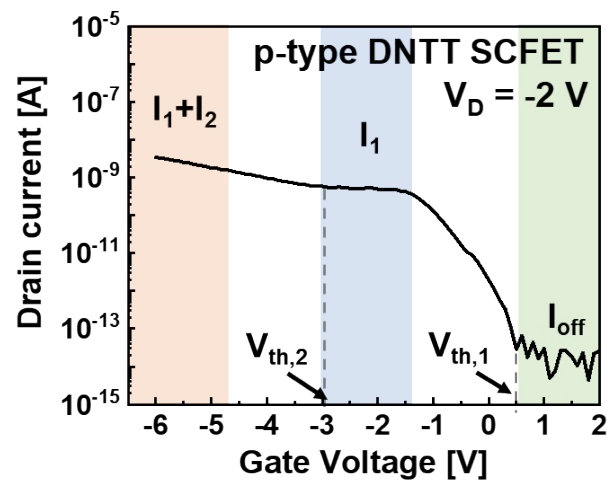


Fig. S4. Experimental I_D - V_G characteristics of p-type dinaphtho[2,3-b:2',3'-f]thieno[3,2-b]thiophene (DNTT) SCFET.